

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

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Title of Invention	HIGH PRESSURE PROCESSING CHAMBER FOR SEMICONDUCTOR SUBSTRATE						
Application Number :	09/912844						
Confirmation Number:	5915						
First Named Applicant:	Maximilian Biberger						
Attorney Docket Number:							
Art Unit:							
Examiner:							
Search string:	(3689025 or 5679169 or 6021791 or 6109296 or 6465403 or 6509141 or 6635565 or 6641678).pn						
Certification: This Information Disclosure Statement was submitted under the following conditions, which satisfies the requirement under 37 CFR 1.97(e). The filer certified:							
That no item of information contained in the information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application, and, to the knowledge of the person signing the certification after making reasonable inquiry, no item of information contained in the information disclosure statement was known to any individual designated in 37 CFR 1.56(c) more than three months prior to the filing of the information disclosure statement.							
US Patent Documents							
Note: Applicant is not required to submit a paper copy of cited US Patent Documents							
init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
1	3689025	1972-09-05	Kiser				
2	5679169	1997-10-21	Gonzales et al.				
3	6021791	2000-02-08	Dryer et al.				
4	6109296	2000-08-29	Austin				
5	6465403	2002-10-15	Skee	B1			
6	6509141	2003-01-21	Mullee	B2			
7	6635565	2003-10-21	Wu et al.	B2			
8	6641678	2003-11-04	DeYoung et al.	B2			
Signature							
Examiner Name				Date			